

## AMENDMENT TO THE SPECIFICATION

Please amend the specification at page 1, paragraph [0001] as follows.

*do not  
enter  
RRB  
11/8/05*

~~[0001] This Application is a Continuation-In-Part of U.S. Patent Application No. 09/752,492, filed December 29, 2000 (now issued as U.S. Patent No. 6,638,580 on October 28, 2003 to Gavish) which is a co-pending application with the current application. The This application is also a divisional of U.S. Patent Application No. 10/209,983, filed July 31, 2002, by Applicants, Ilan Gavish and Yuval Greenzweig, entitled "Focused Ion Beam Deposition" (issued as U.S. Patent No. 6,627,538 on September 30, 2003 to Gavish et al.), which is a continuation of U.S. Patent Application, Serial No. 09/753,108, filed December 30, 2000 ~~now~~ (issued as U.S. Patent No. 6,492,261 on December 10, 2002 to Gavish et al.).~~